PATENT

STATES PATENT AND TRADEMARK OFFICE

In re application

Marc S. Weinberg, et al.

Application No.

08/841,224

Filed

April 29, 1997

For

TRENCHES TO REDUCE CHARGING EFFECTS AND

CONTROL OUT-OF-PLANE SENSITIVITIES IN TUNING

FORK GYROSCOPES AND OTHER SENSORS

Examiner

R. Moller

Attorney's Docket

CSDL1-490XX

Group Art Unit:

2856

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231 on January 27,1999

Registration No. 32,033 Attorney for Applicant(s)

AMENDMENT

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FEB 03 1999

Assistant Commissioner for Patents Washington, D.C. 20231

GROUP 2100

Sir:

In response to the Office Action dated September 28, 1998, please amend the above identified patent application as follows:

In the Specification:

Please amend the specification as follows:

On page 9, line 10, after "etching." insert the following sentence:

-- The trench may also be formed by reactive ion etching, chlorine etching, SF₆ etching, or anisotropic etching. --

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